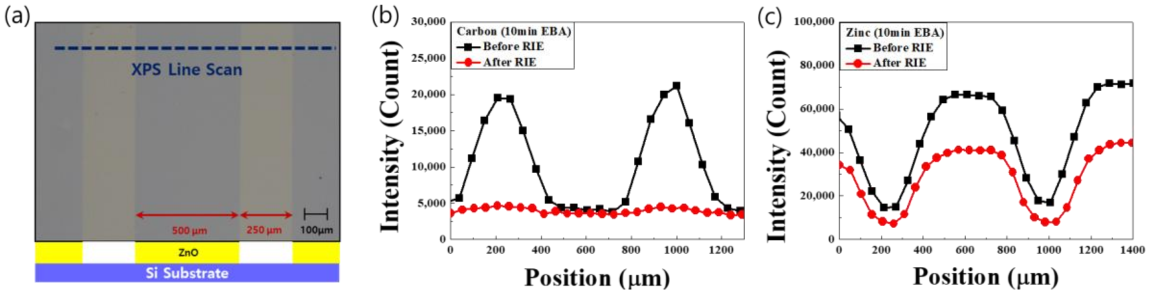

Figure 1 (a) XPS line scan of patterned ZnO OM image. (b) and (c) Carbon and zinc peak intensity position on the patterned ZnO before and after RIE.

Reference

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